

## AMENDMENTS TO THE CLAIMS

Please replace the pending claims with the following claim listing:

1-49. **(Canceled)**

50. **(Currently Amended)** A nitride semiconductor structure comprising on a substrate:  
an n-type collector layer;  
a p-type base layer ~~which is at least one of layers formed on~~ formed over said n-type collector layer;  
an n-type emitter layer formed ~~[[on]]~~ over said p-type base layer;  
an indium-containing p-type nitride semiconductor layer formed directly on ~~[[a]]~~ said p-type base layer so as to contact a top surface of said p-type base layer, ~~which is the top surface having been~~ exposed by etching said n-type emitter layer, wherein said indium-containing p-type nitride semiconductor layer is regrown on said top surface; and  
a base electrode formed ~~[[on]]~~ over said indium-containing p-type nitride semiconductor layer.

51. **(Original)** The nitride semiconductor structure according to claim 50, wherein said p-type nitride semiconductor layer is p-type InGaN.

52. **(Original)** The nitride semiconductor structure according to claim 51, wherein said p-type base layer is p-type InGaN.

53. **(Original)** The nitride semiconductor structure according to claim 51, wherein said p-type InGaN base layer has an indium mole fraction of 5 - 30%.

54. **(Original)** The nitride semiconductor structure according to claim 51, wherein said p-type nitride semiconductor layer has an indium mole fraction higher than an indium mole fraction of said p-type InGaN base layer.

55. **(Original)** The nitride semiconductor structure according to claim 50, wherein said p-type base layer is p-type InGaN.

56. **(Original)** The nitride semiconductor structure according to claim 55, wherein said p-type InGaN base layer has an indium mole fraction of 5 - 30%.

57. **(Original)** The nitride semiconductor structure according to claim 55, wherein said p-type nitride semiconductor layer has an indium mole fraction higher than an indium mole fraction of said p-type InGaN base layer.

58. **(Original)** The nitride semiconductor structure according to claim 50, wherein said p-type InGaN base layer has an indium mole fraction of 5 - 30%.

59. **(Original)** The nitride semiconductor structure according to claim 58, wherein said p-type nitride semiconductor layer has an indium mole fraction higher than an indium mole fraction of said p-type InGaN base layer.

60. **(Original)** The nitride semiconductor structure according to claim 50, wherein said p-type nitride semiconductor layer has an indium mole fraction higher than an indium mole fraction of said p-type InGaN base layer.

61-76. **(Cancelled)**

77. **(Currently Amended)** The nitride semiconductor structure according to claim 50, further comprising a graded layer between said p-type base layer and said n-type collector layer, wherein said graded layer has [[its]] an indium mole fraction varied that varies gradually.

78. **(Currently Amended)** The nitride semiconductor structure according to claim 51, further comprising a graded layer between said p-type base layer and said n-type collector layer, wherein said graded layer has [[its]] an indium mole fraction varied that varies gradually.

79. **(Currently Amended)** The nitride semiconductor structure according to claim 55, further comprising a graded layer between said p-type base layer and said n-type collector layer, wherein said graded layer has ~~[[its]]~~ an indium mole fraction varied ~~that varies~~ gradually.

80. **(New)** The nitride semiconductor structure according to claim 50, wherein the base electrode is formed directly on said indium-containing p-type nitride semiconductor.

81. **(New)** A nitride semiconductor structure comprising:  
an n-type collector layer;  
a p-type base layer formed over said n-type collector layer, the p-type base layer having an etched top surface;  
an n-type emitter layer formed over said p-type base layer;  
an indium-containing p-type nitride semiconductor layer formed directly on the etched top surface of the p-type base layer; and  
a base electrode formed over said indium-containing p-type nitride semiconductor layer.

82. **(New)** The nitride semiconductor structure according to claim 81, wherein said indium-containing p-type nitride semiconductor layer comprises p-type InGaN.

83. **(New)** The nitride semiconductor structure according to claim 81, wherein said p-type base layer comprises p-type InGaN.

84. **(New)** The nitride semiconductor structure according to claim 83, wherein said indium-containing p-type nitride semiconductor layer has an indium mole fraction higher than an indium mole fraction of said p-type base layer.

85. **(New)** The nitride semiconductor structure according to claim 81, further comprising a graded layer between said p-type base layer and said n-type collector layer.